

Docket No.: 55071-328



PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
	:	
Robert John SOCHA, et al.	:	Confirmation Number: 2388
	:	
Serial No.: 10/756,829	:	Group Art Unit: 1756
	:	
Filed: January 14, 2004	:	Examiner: <i>Not yet assigned</i>
	:	
For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE MASK		

INFORMATION DISCLOSURE STATEMENT

Mail Stop Information Disclosure Statement
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

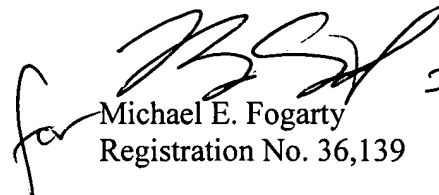
Each reference was first cited in a corresponding foreign application search report or office action and its relevance discussed therein. A copy of the foreign search report or office action, is attached for the Examiner's information.

10/756,829

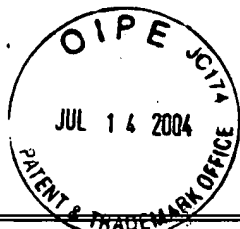
Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT WILL & EMERY LLP

 #46,692
for Michael E. Fogarty
Registration No. 36,139

600 13th Street, N.W.
Washington, DC 20005-3096
(202) 756-8000 MEF:etp
Facsimile: (202) 756-8087
Date: July 14, 2004



SHEET 1 OF 1

INFORMATION DISCLOSURE
CITATION IN AN
APPLICATION

(PTO-1449)

ATTY. DOCKET NO.
55071-328SERIAL NO.
10/756,829APPLICANT
Robert John SOCHA, et al.FILING DATE
January 14, 2004GROUP
[case_group_art]

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code ² (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		US 5,682,323	10/28/1997	Pasch et al.	
		US 5,895,741	04/20/1999	Hasegawa et al.	
		US 6,214,497	04/10/2001	Stanton	
		US 2002-0152452 A1	10/17/2002	Socha	
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FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	CITE NO.	Foreign Patent Document Country Codes-Number 4-Kind Codes (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines Where Relevant Figures Appear	Translation	
						Yes	No
		EP 1 202 119 A1	05/02/2002	ASML masktools Netherlands B.V.			

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		European Search Report (04/15/2004)
		XP-000989124 – MICHAEL S. YEUNG et al.; <u>Optical/Laser Microlithography VI</u> ; Extension of the Hopkins Theory of Partially Coherent Imaging to Include Thin-film Interference Effects; c. 1993; pp.452-463; SPIE Vol. 1927
		XP-002276634 – OLIVIER TOUBLAN et al.; <u>Optical/Laser Microlithography XIV</u> ; Fully Automatic Side Lobe Detection and Correction Technique for Attenuated Phase Shift Masks; c. 2000; pp. 1541-1547; SPIE Vol. 4346
		XP-001187568 – J. A. TORRET et al.; <u>Optical/Laser Microlithography XV</u> ; Contrast-Based Assist Feature Optimization; c. 2002; pp. 179-187; SPIE Vol. 4691
		XP-000869997 – J. FUNG CHEN et al.; Practical I-Line OPC Contact Masks for Sub-0.3Micron Design Rule Application: Part I – OPC Design Optimization; c. 1997; pp. 181-201

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.